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(71) Applicant (for all designated States except US): **LAM RESEARCH AG** [AT/AT]; SEZ-Strasse 1, A-9500 Villach (AT).

(71) Applicant (for BZ only): **LAM RESEARCH CORPORATION** [US/US]; 4650 Cushing Parkway, Fremont, California CA-94538 (US).

(72) Inventor; and

(75) Inventor/Applicant (for US only): **HOHENWARTER, Karl-Heinz** [AT/AT]; Leifling 1, A-9635 Dellach/Gail (AT).

(74) Agent: **KONTRUS, Gerhard**; c/o Lam Research AG, SEZ-Strasse 1, A-9500 Villach (AT).

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Declarations under Rule 4.17:

[Continued on next page]

(54) Title: CLOSED CHAMBER FOR WAFER WET PROCESSING

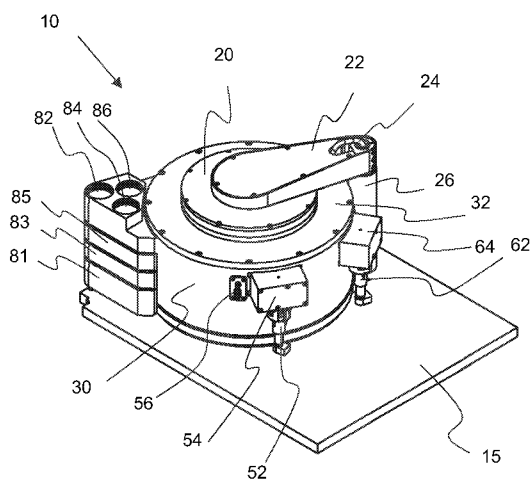


Fig. 1

(57) Abstract: 4303-104 20 ABSTRACT OF THE DISCLOSURE An improved design for a closed chamber process module for single wafer wet processing utilizes a combination lid and gas showerhead for sealing the chamber from above. One or more media arms dispense liquid onto a wafer in the chamber. The media arms are mounted inside the chamber but are connected by a linkage that passes through the chamber wall to a drive unit mounted outside the chamber.



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- *as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii))*
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